

ABSTRACT OF THE DISCLOSURE

PLASMA CVD APPARATUS AND MANUFACTURING METHOD OF MAGNETIC
RECORDING MEDIA

5 [Problems to be solved]

A plasma CVD apparatus capable of forming a high-density and high-hardness thin film on a substrate by lengthening the distance between the cathode and the substrate is provided.

10 [Solution]

The plasma CVD apparatus according to the present invention includes a cathode electrode 3 disposed inside a chamber 2; an anode electrode 4 disposed so as to surround the periphery of the cathode electrode 3; a holding member
15 holding a substrate 1 disposed so as to face the cathode electrode 3 and the anode electrode 4; a plasma wall 8 having a float potential; an AC power supply 5 electrically connected to the cathode electrode 3; a DC power supply 7 electrically connected to the anode electrode 4; and a DC power supply
20 12 electrically connected to the substrate 1, wherein the internal diameter of the cylindrical plasma wall 8 is in the range of 100mm to 200mm inclusive, and the distance between the cathode electrode 3 and the substrate 1 is in the range of 200mm to 300mm inclusive.

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Fig. 1